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Attorney Docket No.: NECW 18.159

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor

: Atsushi NISHIZAWA

Serial No.

: 09/751,979

Filed

: December 29, 2000

Title

: MANUFACTURING METHOD OF SEMICONDUCTOR

INTEGRATED CIRCUIT INCLUDING SIMULTANEOUS

FORMATION OF VIA HOLE REACHING METAL WIRING AND

CONCAVE GROOVE IN INTERLAYER FILM AND

SEMICONDUCTOR INTEGRATED CIRCUIT MANUFACTURED

WITH THE MANUFACTURING METHOD

Examiner

: George A. Goudreau

Group Art Unit

: 1763

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

PETITION FOR EXTENSION OF TIME

SIR:

Applicant requests that the time for taking action in this case be extended pursuant to 37 CFR 1.136(a) for:

[X] one month

[] three months

[] two months

09751979

[] four months

The fee set in 37 CFR 1.17 for the extension of time is \$110.00

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110.00 DA 01 FC:1251

[] Fee enclosed. Please charge an to Deposit Account No. 50-1290. A dupli-	y additional fee required for this extension of time cate copy of this paper is enclosed.
[X] Charge fee to Deposit Accou	ant No. 50-1290. A duplicate copy of this paper
[] Applicant is a small entity entit verified small entity statement:	eled to pay reduced fees in this application. A
[] has been filed	[] is enclosed
Also enclosed is a:	
[X] Response to Official Action [] Notice of Appeal	[] Appeal Brief
	Respectfully submitted,

Michael I. Markowitz Reg. No. 30,659

KATTEN MUCHIN ZAVIS ROSENMAN 575 Madison Avenue New York, New York 10022-2585 (212) 940-8687

Docket No.: NECW 18.159